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CENTRAL FAX CENTERDocket No. 740756-2712
Application No. 10/772,419
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IN THE CLAIMS:

1. (Currently amended) A manufacturing method of a display device, ~~characterized in that comprising:~~

forming a conductive film over a substrate by ejecting liquid droplets containing conductive particles ~~are ejected on a film being processed~~ by using a first liquid droplet ejecting apparatus having comprising a liquid droplet ejecting head provided with a plurality of liquid droplet ejecting nozzles to form a conductive film locally arranged linearly;

forming a resist pattern is locally formed on the conductive film by using a second liquid droplet ejecting apparatus having comprising a liquid droplet ejecting head provided with a plurality of liquid droplet ejecting nozzles arranged linearly; and

forming a wiring by etching the conductive film is etched with the resist pattern as a mask to form a wiring at an atmospheric pressure or a pressure close to the atmospheric pressure by using a plasma generating means comprising one pair of electrodes.

2. (Canceled).

3. (Currently amended) A manufacturing method of a display device according to the ~~manufacturing methods of a display device of claim 1 or 2,~~

wherein after ~~etching the conductive film forming the wiring,~~ the resist film is locally etched at an atmospheric pressure or a pressure close to the atmospheric pressure by using the plasma generating means provided with ~~[[a]] one pair of cylindrical electrodes or the plasma generating means provided with a plurality of pairs of cylindrical electrodes arranged linearly.~~

4. (Currently amended) A manufacturing method of a display device, ~~characterized in that comprising:~~

after forming a conductive film on over a substrate being processed, by ejecting liquid droplets containing conductive particles by using a liquid droplet ejecting apparatus comprising a liquid droplet ejecting head provided with a plurality of liquid droplet ejecting nozzles arranged linearly; and

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after forming the conductive film, forming a wiring by etching an unnecessary portion of the conductive film is locally etched by using a plasma generating means provided with [[a]] one pair of cylindrical electrodes or a plasma generating means provided with a plurality of pairs of cylindrical electrodes arranged linearly at an atmospheric pressure or a pressure close to the atmospheric pressure to form a wiring.

5. (Currently amended) A manufacturing method of a display device, ~~characterized in that comprising:~~

after forming a conductive film on over a substrate being processed by using a liquid droplet ejecting apparatus having comprising a liquid droplet ejecting head provided with a plurality of liquid droplet ejecting nozzles arranged linearly; and [[,]]

forming a resist pattern on the conductive film;

after forming the resist pattern, forming a wiring by etching an unnecessary portion of the conductive film is locally etched by using a plasma generating apparatus means provided with [[a]] one pair of cylindrical electrodes or a plasma generating means provided with a plurality of pairs of cylindrical electrodes arranged linearly at an atmospheric pressure or a pressure close to the atmospheric pressure to form a wiring.

6. (New) A manufacturing method of a display device according to claim 1, wherein the wiring includes at least one conductive material selected from the group consisting of Ag, Au, Cu, Ni, Pt, Pd, Ir, Rh, W, and Al, metal sulfide of Cd and Zn, oxide of Fe, Ti, Si, Ge, Si, Zr, Ba, and the like, and fine particles or dispersible nanoparticles of silver halide.

7. (New) A manufacturing method of a display device according to claim 4, wherein the wiring includes at least one conductive material selected from the group consisting of Ag, Au, Cu, Ni, Pt, Pd, Ir, Rh, W, and Al, metal sulfide of Cd and Zn, oxide of Fe, Ti, Si, Ge, Si, Zr, Ba, and the like, and fine particles or dispersible nanoparticles of silver halide.

8. (New) A manufacturing method of a display device according to claim 5, wherein the wiring includes at least one conductive material selected from the group consisting of Ag, Au, Cu, Ni, Pt, Pd, Ir, Rh, W, and Al, metal sulfide of Cd and Zn, oxide of Fe, Ti, Si, Ge, Si,

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Zr, Ba, and the like, and fine particles or dispersible nanoparticles of silver halide.

9. (New) A manufacturing method of a display device according to claim 5, wherein after forming the wiring, the resist film is etched at an atmospheric pressure or a pressure close to the atmospheric pressure by using the plasma generating means provided with one pair of electrodes.

10. (New) A manufacturing method of a display device according to claim 1, wherein the one pair of electrodes are cylindrical electrodes.

11. (New) A manufacturing method of a display device according to claim 4, wherein the one pair of electrodes are cylindrical electrodes.

12. (New) A manufacturing method of a display device according to claim 5, wherein the one pair of electrodes are cylindrical electrodes.

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